

# Validation of a plasma sheath model for use in RF sputtering systems.

The Author] - Sputtering



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**Bibliographies: 'RF superimposed DC sputtering, transparent conductive oxides (TCO)'**

The measured heat flux patterns along the poloidal limiters surrounding powered antennas were compared to predictions from a simple RF sheath rectification model. Using magnetron sputtering deposition technique, we prepared preferential orientation ITO thin films on quartz substrate.

**Книги:**

Thermal stability is confirmed at 700°C in vacuum for 3 hours.

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The heat spike sputtering often increases nonlinearly with energy, and can for small cluster ions lead to dramatic sputtering yields per cluster of the order of 10,000.

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Nickel oxide NiO is a good candidate for this application as it has desired properties such as good hole conduction, a high band gap and a matching work function to the perovskite. It is revealed that the performance of the absorber is improved by fabricating microstructures on the metal substrate.

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